

Notice of References Cited	Application/Control No. 10/557,694	Applicant(s)/Patent Under Reexamination HADA ET AL.	
	Examiner Anca Eoff	Art Unit 1709	Page 1 of 1

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*	B	US-6,358,665	03-2002	Pawlowski et al.	430/270.1
*	C	US-2003/0049456	03-2003	Kawasato et al.	428/421
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	M	US-			

FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.